Aluminium Doped TiO_v (TiO_v:Al): Improving Surface Passivation on Si by **Supressing Crystal Phase Transformation**

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- \checkmark TiO_x is a possible alternative to the Al₂O₃/SiN_x:H stack for passivating p+ Si surfaces
- \checkmark TiO, provides both anti-reflection and surface passivation in a single package
- \checkmark TiO_x is an excellent ARC for solar cells due to its high reflective index *n* and lower parasitic light absorption (below 600nm) than SiN_x:H due to its lower extinction coefficient k
- \checkmark Surface passivation of TiO_x deteriorates when the layer is thick or being annealed at elevated temperatures, which is due to a phase transition from amorphous to anatase

 \checkmark This work presents improved surface passivation and thermal stability of TiO_x via AI doping of the film which inhibits

crystal phase transformation

D Experiments and results

> Undoped TiO,

 10^{0}

20

> Al doped TiO_x (TiO_x:Al) **10⁵** face recombination factor J_{0s} (fA/cm²) 10⁴ 10¹ 10² 10¹ 1 (fA/cm^2) Thickness sensitive FGA 250°C As dep FGA 250°C FGA 300°C As dep FGA 350°C FGA 300°C more than 10nm: no passivation FGA 400°C FGA 350°C FGA 400°C **10**⁴ Unstable up to annealing 15nm TiO_x:Al J_{0s} @ 250°C where J_{0s} increases Incompatible with cell fabrication cto **10³** recombinati 10² Improved passivation J_{0s} : 110 fA/cm², SRV:15 cm/s 10 Improved thermal robustness @350°C showing the lowest J_{0s} rface

Compatible with cell fabrication



Two theta (degree)

30

 \checkmark A small increase in TiO_x thickness can trigger a phase change from amorphous TiO_x into anatase \checkmark Al doping into the TiO_x films inhibits crystallization \checkmark Doping could be a promising strategy to improve the surface passivation quality and the thermal stability of TiO_x

40 300 400 700 800 900 500 600 1000

Wavelength (nm)

 \checkmark n and k were modelled using the Caushy model with ellipsometry test \checkmark Very low k value (< 0.1) measured for undoped and doped TiO_{v} \checkmark n value decreases with doping, but also maintains n = 2.33 @ 632 nm

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